AMENDMENTS TO THE CLAIMS

1. (Currently amended) A negative type resist composition comprising [alkali soluble resin,] polyvinyl phenol-based resin in which the phenolic hydroxyl group is partially alkyletherified, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)

wherein, A represents sulfide group or, disulfide group [or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, sulfide group, or disulfide group,] X represents nitrogen atom [or C(NH₂)], and R¹ and R² independently represent hydrogen or alkyl [provided that, when X represents C(NH₂), A represents sulfide group or disulfide group].

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):

$$R^{1}$$
 $A \leftarrow X$
 (Ia)

wherein, A, X, R¹ and R² are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

- 3. (Canceled)
- 4. (Canceled)

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- 5. (Canceled)
- 6. (Canceled)
- 7. (Previously Presented and Amended) The negative type resist composition according to [claim 6] claim 1, wherein the basic compound of formula [Ib] (1) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.
 - 8. (Canceled)
- 9. (Original) The negative type resist composition according to claim 1, wherein the acid generator is a sulfonic ester of N-hydroxyimide compound.
- 10. (Currently Amended) The negative type resist composition according to claim 1, 2, 7, or 9, wherein composition ratio of the basic compound of formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.
 - 11. (Cancelled)
 - 12. (Cancelled)
 - 13. (Cancelled)